

Amendments to the Claims:

1. (Currently Amended) A washing apparatus for washing a crystal suspension of crystals, said washing apparatus comprising:

- a material conveying means comprising an outlet and a connection to a First Region and further comprising a pump wherein the material conveying means supplies a wash material to the First Region;
- ~~a First Region, to which [[a]]the wash material is supplied by a wash material conveying means is provided upstream of the First Region or at least partially in the First Region wherein the wash material conveying means has an outlet, and a pressure at the outlet of the wash material conveying means wherein the pressure fluctuates about not less than about 0.5 bar and wherein the crystal suspension has a viscosity of less than 250mPas and the crystals have an average diameter of not more than 1500µm,~~
- a Second Region, in which the wash material is washed, said Second Region comprising a washing column having a diameter of at least about 300 mm or greater, and wherein the Second Region may reach a pressure from about 0.1 to about 30 bar,
- a Third Region, in which the wash material is melted wherein the Third Region comprises a heat exchanger wherein the temperature of said heat exchanger is not more than 5°C above the melting point of the target product, and
- ~~a flow resistorresistance provided between~~ a flow resistorresistance is arranged in a stationary position between the Second Region and the Third Region and is non-rotatable about a central longitudinal axis of the Second Region, wherein the flow ~~resistorresistance includes at least one opening~~ comprises multiple openings wherein each opening includes an “A” cross-section facing the Second Region and a “B” cross-section facing the Third Region wherein the “A” cross-section facing the Second Region is at least 10 times larger than the “B” cross-section facing the Third Region;

~~wherein the Second Region is at least partially in the form of a column, wherein this column has a diameter of at least about 300 mm or greater, and wherein the Second Region may reach a pressure from about 0.1 to about 30 bar.~~

2. (Canceled) ~~The washing apparatus according to claim 1, wherein the flow resistance is arranged non-rotatable about a central longitudinal axis of the Second Region.~~

3. (Previously Presented) The washing apparatus according to claim 2, wherein there is provided between the First Region and the Second Region a solid/liquid separation apparatus having a filtrate offtake line.

4. (Previously Presented) The washing apparatus according to claim 3, wherein the solid/liquid separation apparatus is in the form of a filter in a wall adjacent to the Second Region.

5. (Previously Presented) The washing apparatus according to claim 4, wherein the wall is arranged at an angle α in the range from 0 to less than about 90°, relative to the central longitudinal axis.

6. (Cancelled)

7. (Previously Presented) The washing apparatus according to claim 1, wherein the flow resistance is characterized by a relative free cross-sectional area in the range from 0 to less than about 100 %, relative to the total area of the flow resistance.

8. (Previously Presented) The washing apparatus according to claim 7, wherein the free cross-sectional area is variable.

9. (Previously Presented) The washing apparatus according to claim 7 wherein the flow resistance can be tempered.

10. (Cancelled)

11. (Previously Presented) The washing apparatus according to claim 1, wherein the conveying means free of pulsation has a conveyor spiral.

12. (Cancelled)

13. (Currently Amended) A purification apparatus comprising a crystal-producer that is connected in a crystal-carrying way with the First Region of a washing apparatus, said purification apparatus comprising:

- a material conveying means comprising an outlet and a connection to a First Region and further comprising a pump wherein the material conveying means supplies a wash material to the First Region;
a First Region, to which ~~[[a]]the~~ wash material is supplied ~~by a wash material conveying means is provided upstream of the First Region or at least partially in the First Region wherein the wash material conveying means has an outlet, and a pressure at the outlet of the wash material conveying means wherein the pressure fluctuates about not less than about 0.5 bar and wherein the crystal suspension has a viscosity of less than 250mPas and the crystals have an average diameter of not more than 1500µm,~~
-a Second Region, in which the wash material is washed, said Second Region comprising a washing column having a diameter of at least about 300 mm or greater, and wherein the Second Region may reach a pressure from about 0.1 to about 30 bar,
- a Third Region, in which the wash material is melted, and
- a flow ~~resistor~~resistance provided between, for compacting the wash material without the wash material blocking the flow resistor; wherein the flow resistor is arranged in a stationary position

between the Second Region and the Third Region and is non-rotatable about a central longitudinal axis of the Second Region;

wherein the flow ~~resistor~~resistance includes at least one openingcomprises multiple openings

wherein each opening includes an “A” cross-section facing the Second Region and a “B” cross-section facing the Third Region wherein the “A” cross-section facing the Second Region is at least 10 times larger than the “B” cross-section facing the Third Region, wherein said Second Region may reach a pressure from about 0.1 to about 30 bar; and

wherein the apparatus further comprises a heat exchanger wherein the temperature of said heat exchanger is not more than 5°C above the melting point of the target product.

14. (Previously Presented) The purification apparatus according to claim 13, wherein a dwell-time container is provided between the crystal-producer and the washing apparatus.

15. (Previously Presented) A synthesis device comprising a synthesis installation and downstream a purification apparatus as defined in claim 13.

16. (Previously Presented) The synthesis device according to claim 15, wherein the synthesis installation is a gaseous phase oxidation synthesis unit.

17. (Previously Presented) A method of purifying a wash material, wherein the wash material is supplied by way of the First Region of a washing apparatus defined in claim 1 and a target product is obtained.

18. (Previously Presented) The method according to claim 17, wherein the wash material contains at least about 20 % of the target product by weight.

19. (Previously Presented) A product selected from the group consisting of food, polymers, fuels, lubricants, cleaning agents, dyes and pharmaceuticals comprising target product made by the method of claim 17.

20. (Previously Presented) A product selected from the group consisting of food, monomers, fuels, solvents, waste-water treatment, and isomer separation prepared by a purification apparatus of claim 13.

21. (Previously Presented) The washing apparatus according to claim 1, wherein the wash material is a crystal suspension comprising acrylic acid wherein the concentration of the acrylic acid in the crystals is at least about 90% by weight.

22. (Previously Presented) The washing apparatus according to claim 21, wherein the crystal suspension consists of crystals or a liquid phase.

23. (Previously Presented) The purification apparatus according to claim 13, wherein the wash material is a crystal suspension comprising acrylic acid wherein the concentration of the acrylic acid in the crystals is at least about 90% by weight.

24. (Cancelled)